Gencoa planar rectangular magnetrons cover a range of robust and reliable cathodes, configurable with the widest choice of magnetic and mechanical options on the market. With high performance and low maintenance, all products benefit from Gencoa's process knowhow and implementation service.

**KEY FEATURES**
1. Robust with choice of optimized magnetics tuned to any application
2. High power RF/Hipims standard electrical insulation
3. Two water inputs/outputs with turbulent flow for high power
4. Zero-height anodes and sputter to target edge to prevent shorts and arcing
5. Integral anodes with option of water cooling or zonal gas injection

Perfect your process
www.gencoa.com
Gencoa have pioneered the control of magnetic field interactions with anodes to enhance processes. Single and multiple magnetron arrangements are modelled and optimised as part of our customer service. High energy plasma assistance within chambers with DC or Hipims power modes are a speciality.

Multipole magnetic array designs to flatten the field over the target surface for >40% target utilization to increase machine up-time and reduce material costs.

A wide range of adjustable magnetic arrays are available that match more demanding applications: VT, VTR, VTFlex, VTS. Dynamic adjustment of balance, strength and uniformity.

Sputtering of Nickel (up to 6mm) or Iron (up to 2mm) can be achieved with high strength (HS) magnetics. Gencoa’s Loop option enables a custom magnetic arrangement for even thicker ferromagnetic materials. Sources have special clamps to install/lift the target away.

The XH magnetic system is available for 150mm wide targets, and uses dynamic variable speed lateral movement to scan the plasma and sputter the entire surface - increasing the target use to 50-70% depending upon target details.

FURTHER INFORMATION
Contact: sales@gencoa.com or visit www.gencoa.com/rectangular